

Synthesis and Characterization of titanium nitride by RF magnetron sputtering

Titanium nitride coatings have been used very successfully in a variety of applications because of their excellent properties, such as hard and decorative coatings and also diffuse barriers in semiconductor technology. This paper aim to find optimize deposition conditions of Titanium nitride thin film on the glass substrate and focuses on characterization by RF magnetron sputtering technique. The proper plasma conditions used to deposit Titanium nitride film were carried out by the optical emission spectroscopy (OES).The film physical properties will be analyzed by X-ray diffraction (XRD)

Keyword: titanium nitride,thin film,RF magnetron sputtering

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